TSMC-03-485

April 9, 2004

To: Commissioner for Patents
P.O.Box 1450
Alexandria, VA 22313-1450

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Subject: Serial No. 10/780,513 02/17/04

Bor-Wen Chan et al.

A METHOD TO FORM A METAL SILICIDE GATE DEVICE

INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation In An Application.

The following Patents and/or Publications are submitted to comply with the duty of disclosure under CFR 1.97-1.99 and 37 CFR 1.56.

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on April 12, 2004.

Stephen B. Ackerman, Reg.# 37761

Signature/Date 4/12/04

U.S. Patent 6,465,309 to Xiang et al., "Silicide Gate Transistors," describes a method to form a silicide gate transistor.

U.S. Patent 6,475,908 to Lin et al., "Dual Metal Gate Process: Metals and Their Silicides," describes a method to form metal silicide gate MOS transistors.

U.S. Patent 6,528,402 to Tseng, "Dual Salicidation Process," describes a method to form a self-aligned, silicide gate.

Sincerely,

Stephen B. Ackerman,
Reg. No. 37761

Form PTO-1449

INFORMATION DISCLOSURE CITATION IN AN APPLICATION

(Use several sheets if necessary)

Docket Number (Optional)	Application Number
TSMC-03-485	10/780,513
Applicant: Bor-Wen Chan et al.	
Filing Date: 02/17/04	Group Art Unit

U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date if Appropriate
	6465309	10/15/02	Xiang et al.	438	299	12/12/00
	6475908	11/5/02	Lin et al.	438	659	10/18/01
	6528402	3/4/03	Tseng	438	592	2/23/01

FOREIGN PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation YES	Translation NO

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER	DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant